

Application No. 10/586,445  
Amdt. dated 18 November 2010  
Reply to Office Action of 19 August 2010

**Amendments to the Claims:**

This listing of claims will replace all prior versions, and listings, of claims in the application:

**Listing of Claims:**

Claims 1-7 Cancelled

8. (new) A method for predicting a precipitation behavior of oxygen in a silicon single crystal for predicting behavior of oxygen precipitates produced in the silicon single crystal in response to heat treatment, comprising:

dividing a heat treatment process into a plurality of time segments;

determining a nucleation rate  $I(T, C, TD)$  of the oxygen precipitates in each time segment from a nucleation rate formula,

$$I(T, C, TD) = a(T)C^9 TD^{1/3}$$

wherein  $I(T, C, TD)$  is the nucleation rate ( $cm^{-3} s^{-1}$ ),  $C$  is an oxygen concentration ( $\times 10^{17} cm^{-3}$ ),  $TD$  is a thermal donor concentration ( $\times 10^{15} cm^{-3}$ ),  $T$  is a temperature;  $a(T)$  is a constant determined by the temperature; and

determining a density of nuclei  $N(t')$  of the oxygen precipitates produced during a period  $\Delta t$  that begins at the time  $t'$ , from a formula,

$$N(t') = I(T, C, TD)\Delta t.$$

Application No. 10/586,445  
Amdt. dated 18 November 2010  
Reply to Office Action of 19 August 2010

9. (new) The method according to claim 8, further comprising:

determining a growth rate  $R(t', t)$  in time  $t$  of nuclei of the oxygen precipitates produced during the period  $\Delta t$  that begins at time  $t'$ , from a formula,

$$\frac{\partial R(t', t)}{\partial t} = \frac{DV}{2R(t', t)}(C - Ci)$$

In which  $Ci = C^{eq} \exp\left(\frac{V\sigma}{RkT}\right)$

wherein  $R(t', t)$  is a radius in the time  $t$  of the nuclei of the oxygen precipitates produced during the period  $\Delta t$  that begins at time  $t'$ , and  $Ci$  is an equilibrium oxygen concentration at an interface of spherical particles with a radius  $R$ , and

determining an amount of precipitated oxygen from a formula,

$$\frac{\partial C}{\partial t} = -4\pi D \int_{t'=0}^{t'=t} N(t') R(t', t)(C - Ci) dt'.$$

Application No. 10/586,445  
Amdt. dated 18 November 2010  
Reply to Office Action of 19 August 2010

10. (new) The method according to claim 8, further comprising:

determining the thermal donor concentration  $TD$  at the temperature  $T_2$  from 400°C to 550°C which the silicon single crystal undergoes during crystal growth, from a formula,

$$TD = TD(T_2)^{eq} \{1 - \exp(-aDC(t_{12} + t))\}$$

wherein  $TD$  is the thermal donor concentration ( $\times 10^{15} \text{ cm}^{-3}$ ),  $TD^{eq}$  is a thermal equilibrium concentration of the thermal donor concentration,  $a$  is a coefficient ( $=9.0 \times 10^{-50}$ ),  $k$  is a Boltzmann's constant,  $D$  is a diffusion constant of oxygen,  $C$  is the oxygen concentration,  $t$  is the time, and  $t_{12}$  is an equivalent time required for generation at the constant temperature  $T_2$  of an amount of thermal donors generated during cooling to the temperature  $T_2$ .

Application No. 10/586,445  
Amdt. dated 18 November 2010  
Reply to Office Action of 19 August 2010

11. (new) A storage medium for storing a program for predicting by a computer a behavior of oxygen precipitates produced in a silicon single crystal in response to heat treatment, wherein the storage medium stores the following processing as the program:

processing in which

a heat treatment process is divided into a plurality of time segments, and

a nucleation rate  $I(T,C,TD)$  of the oxygen precipitates in each time segment is determined from a nucleation rate formula:

$$I(T,C,TD)=a(T)C^9TD^{1/3}$$

wherein  $I(T, C, TD)$  is the nucleation rate ( $cm^{-3}s^{-1}$ ),  $C$  is an oxygen concentration ( $\times 10^{17} cm^{-3}$ ),  $TD$  is a thermal donor concentration ( $\times 10^{15} cm^{-3}$ ),  $T$  is a temperature;  $a(T)$  is a constant determined by the temperature; and

processing in which a density of nuclei  $N(t')$  of the oxygen precipitates produced during a period  $\Delta t$  that begins at time  $t'$ , is determined from a formula,  
 $N(t')=I(T,C,TD) \Delta t.$

Application No. 10/586,445  
Amdt. dated 18 November 2010  
Reply to Office Action of 19 August 2010

12. (new) The storage medium for storing a program according to claim 11, wherein the storage medium further stores the following processing as the program:

processing in which a growth rate  $R(t',t)$  in time  $t$  of the nuclei of the oxygen precipitates produced during the period  $\Delta t$  that begins at time  $t'$ , is determined from a formula,

$$\frac{\partial R(t',t)}{\partial t} = \frac{DV}{2R(t',t)}(C - Ci)$$

In which  $Ci = C^{eq} \exp\left(\frac{V\sigma}{RkT}\right)$

wherein  $R(t',t)$  is a radius in the time  $t$  of the nuclei of the oxygen precipitates produced during the period  $\Delta t$  that begins at time  $t'$ , and  $Ci$  is an equilibrium oxygen concentration at an interface of spherical particles with a radius  $R$ ; and

processing in which an amount of precipitated oxygen is determined from a formula,

$$\frac{\partial C}{\partial t} = -4\pi D \int_{t'=0}^{t'=t} N(t') R(t',t) (C - Ci) dt' .$$

Application No. 10/586,445  
Amdt. dated 18 November 2010  
Reply to Office Action of 19 August 2010

13. (new) The storage medium for storing a program according to claim 11, wherein the storage medium further stores the following processing as the program:

processing in which the thermal donor concentration  $TD$  at the temperature  $T_2$  from 400°C to 550°C which the silicon single crystal undergoes during crystal growth, is determined from a formula,

$$TD = TD(T_2)^{eq} \{1 - \exp(-aDC(t_{12}+t))\}$$

wherein  $TD$  is the thermal donor concentration ( $\times 10^{15} \text{ cm}^{-3}$ ),  $TD^{eq}$  is a thermal equilibrium concentration of the thermal donor concentration,  $a$  is a coefficient ( $=9.0 \times 10^{-50}$ ),  $k$  is a Boltzmann's constant,  $D$  is a diffusion constant of oxygen,  $C$  is the oxygen concentration,  $t$  is the time, and  $t_{12}$  is an equivalent time required for generation at the constant temperature  $T_2$  of an amount of thermal donors generated during cooling to the temperature  $T_2$  occurs.